Active Research and Consultancy in

PULSED DC MICROWAVE ACTIVATED PLASMA ASSISTED MAGNETRON SPUTTERING

Pulsed DC magnetron microwave plasma magnetron sputtering system. Drum based system, accommodating up to sixteen 4" diameter wafers, achieving $\pm 1\%$ thickness uniformity. Deposits metals, oxides, nitrides, carbides, transparent conductive oxides.



Technique produces high density, stable, adherent coatings at room temperatures.





Graded index coatings possible using pulsed DC microwave plasma sputtering, illustrated as follows:



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